

# ABSTRACT

A novel polymer is obtained by copolymerizing a  
5 (meth)acrylic acid derivative with a vinyl ether compound,  
an allyl ether compound and an oxygen-containing alicyclic  
olefin compound. A resist composition comprising the  
polymer as a base resin is sensitive to high-energy  
radiation, has excellent sensitivity, resolution, etching  
10 resistance, and minimized swell and lends itself to  
micropatterning with electron beams or deep-UV.

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